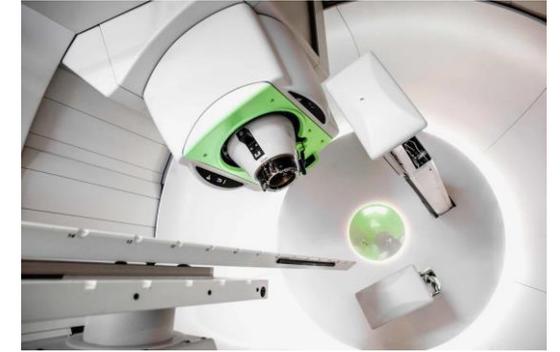
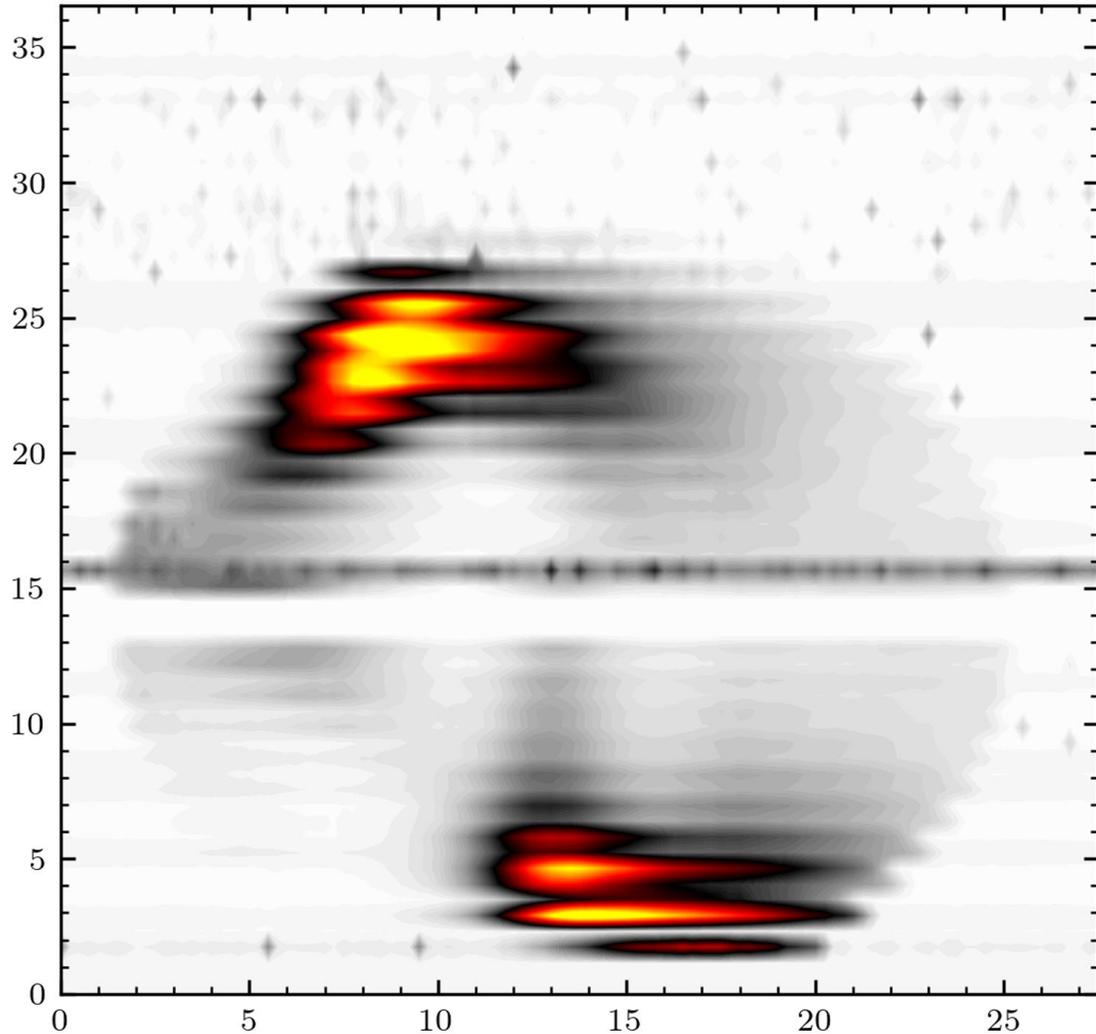


MATRIX : VERS DE L'IMAGERIE PROTONS



wpc West German
Proton Therapy Centre
Essen

CRHEA

RUB

ii!!!

MATRIX

Antoine Lacassagne
CENTRE DE LUTTE CONTRE LE CANCER
unicancer NICE

iPHC
Institut Pluridisciplinaire
Hubert CURIE
STRASBOURG

**Université
franco-allemande
Deutsch-Französische
Hochschule**

MATRIX : GaN diode array for proton monitoring and imaging

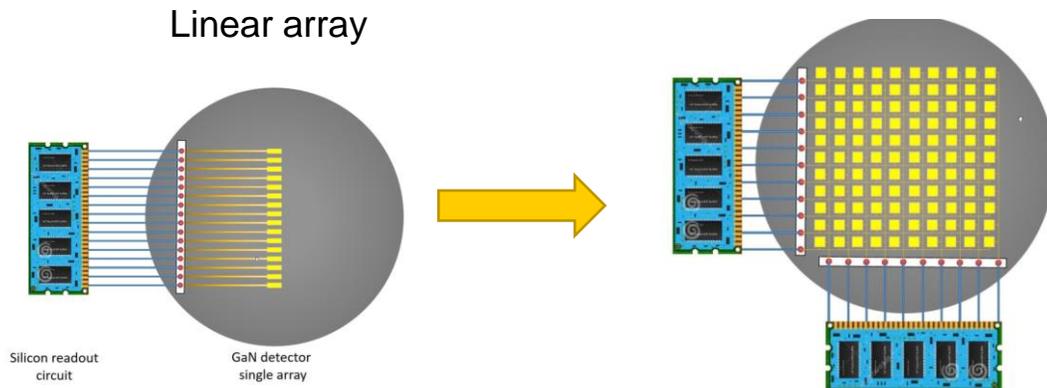
ANR

- CRHEA, Nice : GaN design
- CAL, Nice : test facility, MEDICYC proton line, 65 MeV, Proteus One, 230 MeV
- Ruhr-University, Bochum : GaN tests
- West German Proton Therapy Center, Essen : test facility, 230 MeV

→ IPHC, Strasbourg (from the detector to the signal)

Roadmap :

- GaN diode selection / process ▲
- Laser / proton beam tests → selection (yield) ▲
- DAQ (cots if possible) ▲
- Linear array of 64 diodes ▲
- Proton beam tests ▲
- Matrix (11x11) diodes
- MATRIX (128 x 128)
- Applications



2-D imaging array
36 cm² (500 μm² diode)
128 x 128 diodes
Current integration from the chip

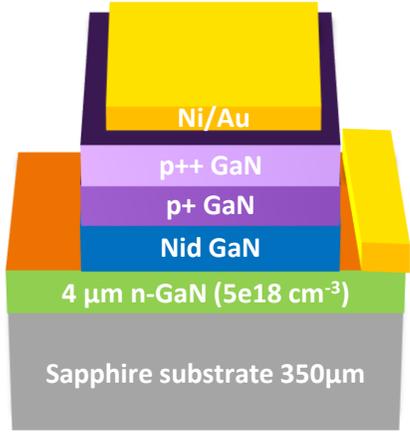
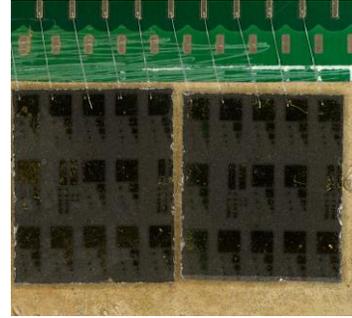
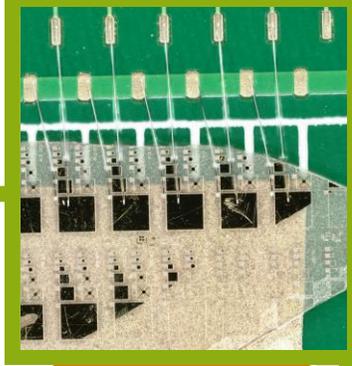
Why GaN ?

| | Bandgap (eV) | Breakdown field (MV/cm) | Electron mobility (cm ² /Vs) | Thermal conductivity (W/mK) | Radiation hardness | Large area (industry) | Cost |
|---------|--------------|-------------------------|---|-----------------------------|--------------------|-----------------------|------|
| SiC | 2.36-3.23 | 3.5 | 900 | 320 | + | + | - |
| GaN | 3.4 | 3.4 | 1500 | 1300 | + | + | - |
| Si | 1.1 | 10 | 3000 | 230 | - | + | -- |
| Diamond | 5.47 | 0.3 | 1500 | 2130 | + | - | + |



INVESTIGATING DIODES STRUCTURES (500 μm^2 diode)

courtesy of M. Siviero (CRHEA)



Substrate:

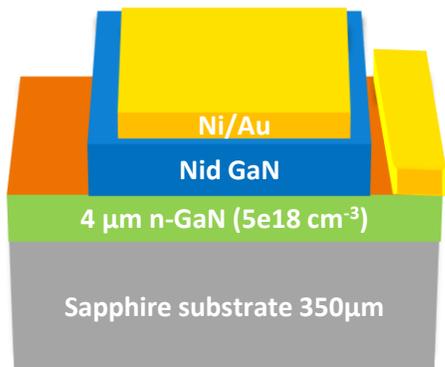
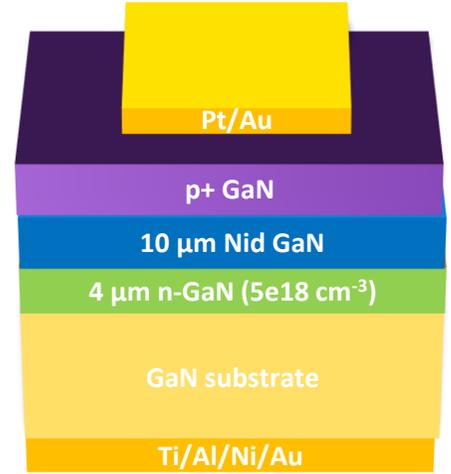
- Sapphire cheaper than GaN
- GaN has no lattice mismatch

PIN on sapphire
10 μm nid GaN

PIN on GaN
10 μm nid GaN

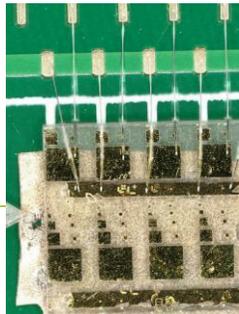
PIN diodes:

- require Mg⁺ doping



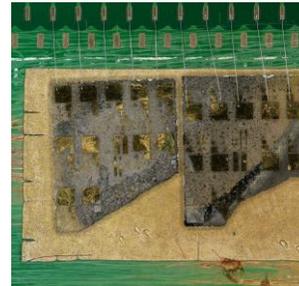
Schottky diodes:

- No Mg⁺



Schottky on Sapphire
1,2,4,10 μm nid GaN

Schottky on GaN
10 μm nid GaN



INVESTIGATING DIODES STRUCTURES cont'd

Substrate: no effect observed on the dark current nor the response to protons
Sapphire substrates **needed** for medium and large size arrays → 3" wafers
⇒ **Sapphire substrate**

Pin shows :

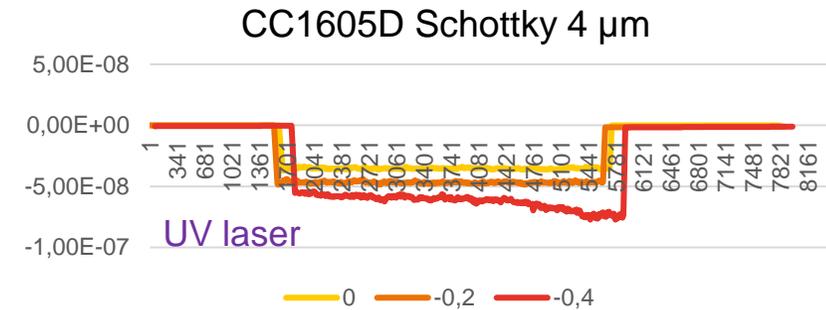
- higher responses
 - lower dark current
 - less response instability
 - higher process yield than Schottky diodes
- ⇒ **pin diodes**

Thickness of undoped active region :

- Schottky: no clear trend among samples with $L=1-2-4-10\mu\text{m}$
- pin: samples with $L=1-2-4-10\mu\text{m}$.
Similar results for 2 and $10\mu\text{m}$. $4\mu\text{m}$ to be measured
 $10\mu\text{m}$ very difficult to process

⇒ **Thickness will be in the range 1-2 μm** : processing yield is a key issue for arrays !

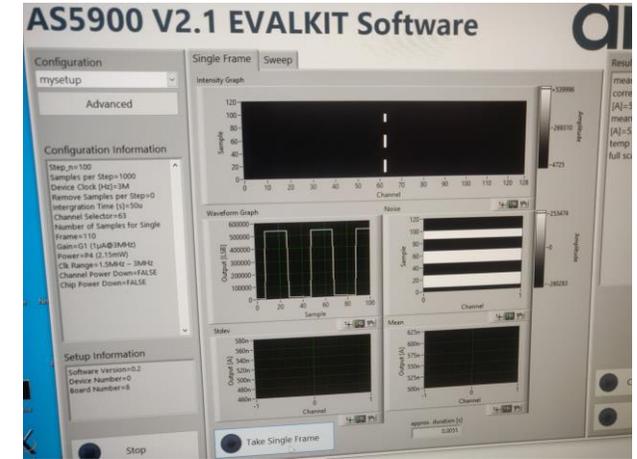
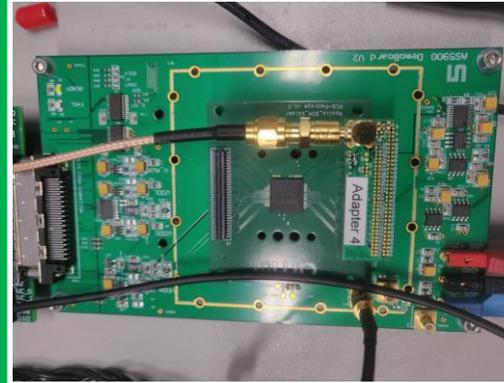
courtesy of J-Y. Duboz (CRHEA)



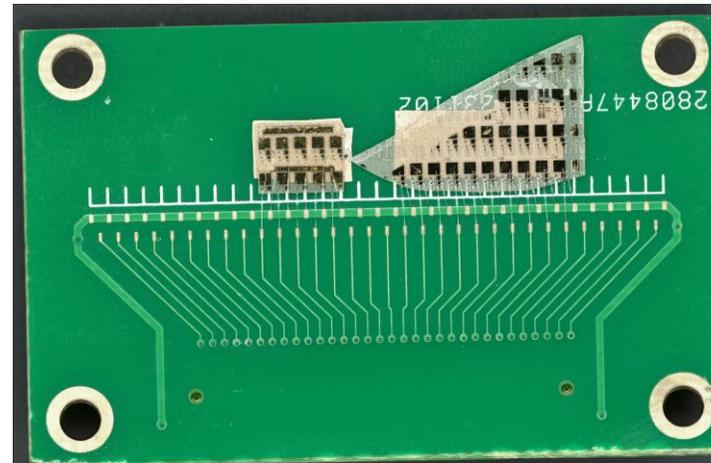
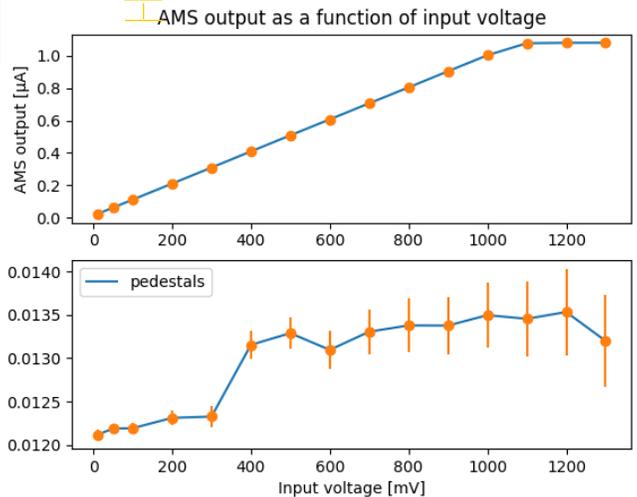
ACQUISITION SYSTEM

COTS (Market survey)

- N channels (~128)
- Current input (up to 1ms), low noise
- Xray imaging (radiotherapy)
 - Analog devices (in progress)
 - **AMS-OSRAM (NDA)**
 - **AS5900** – 26 bit 128 Channel Low Noise Current-to-Digital



Closed software : biasing, etc.



14 channels :

- average of 10000 tests, 10s
- 1ms integration time
- 9 pin diodes 1606D0
- 5 Schottky diodes 1517A2
- Mean of mean : 422 pA 😊
- Std : 350 fA

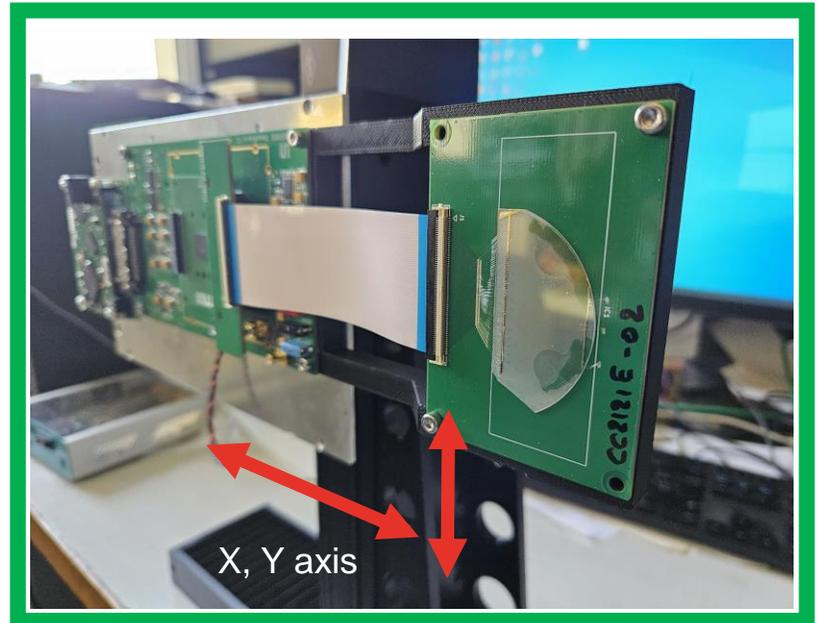
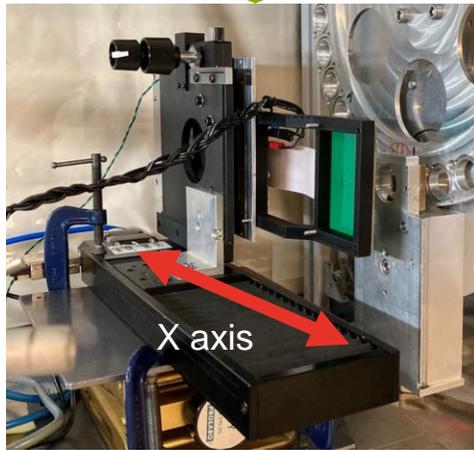
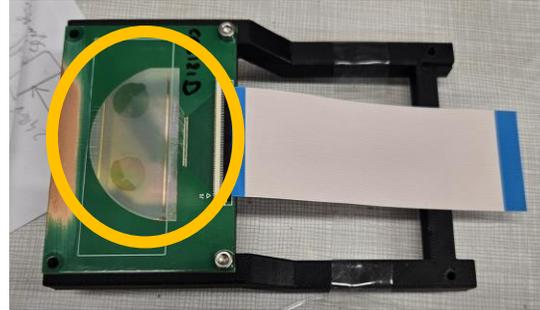
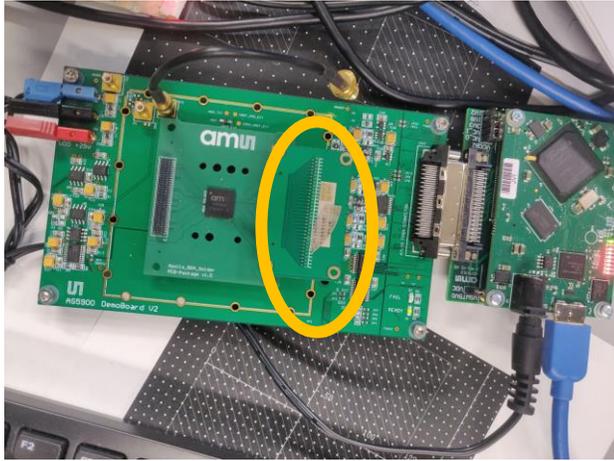
2 dead channels



EVOLUTION OF THE SETUP

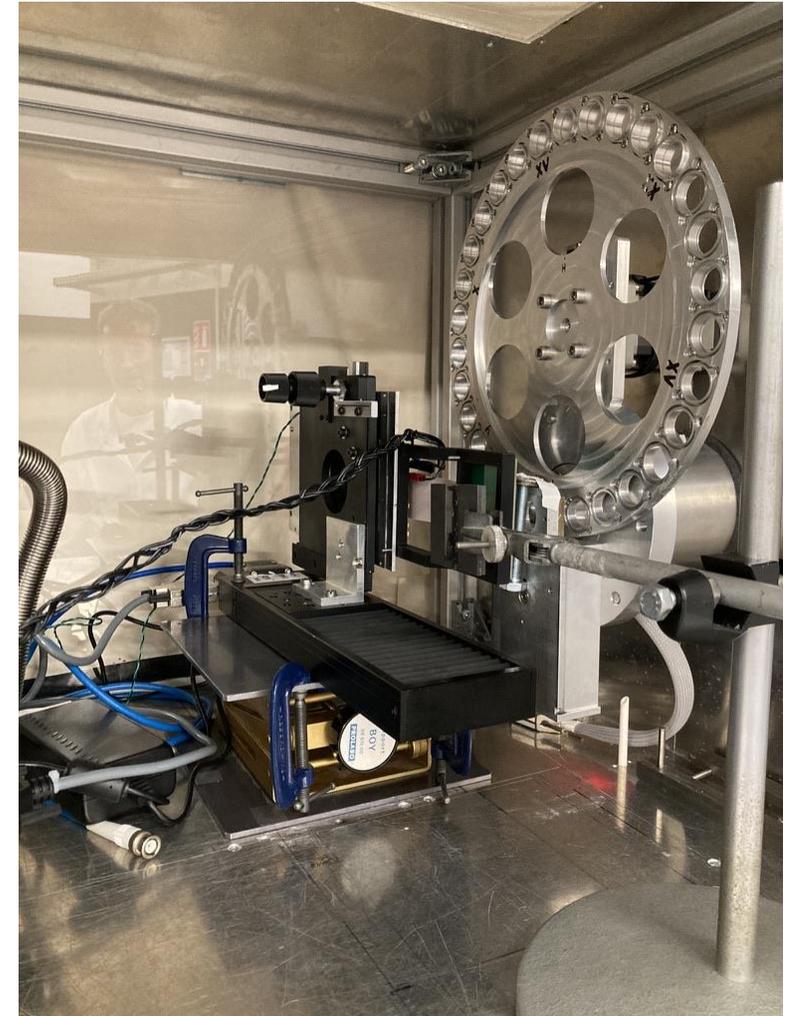
FROM

TO

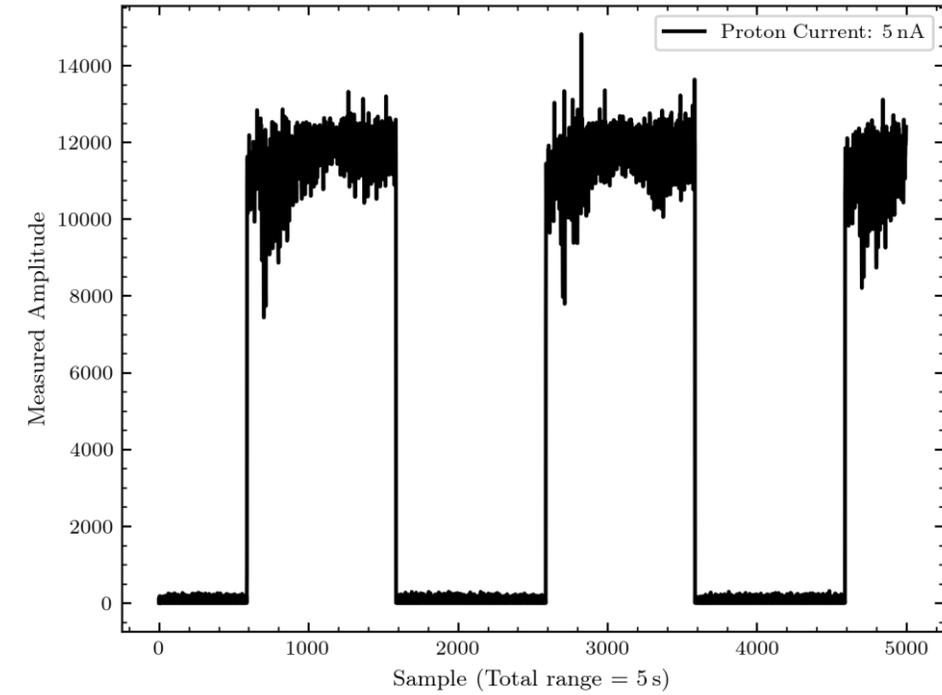


CYRCE EXPERIMENT

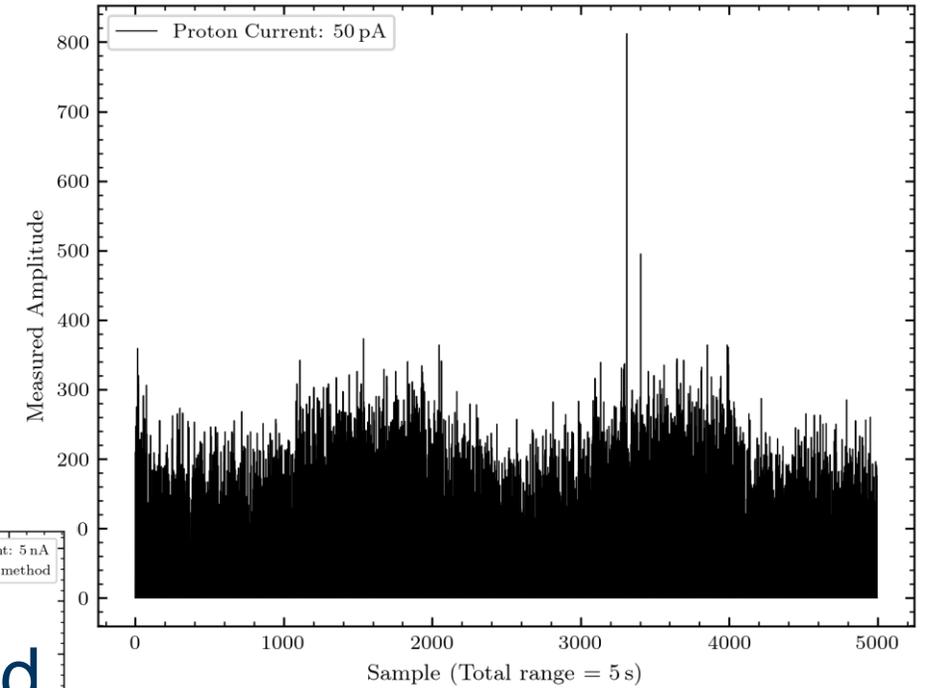
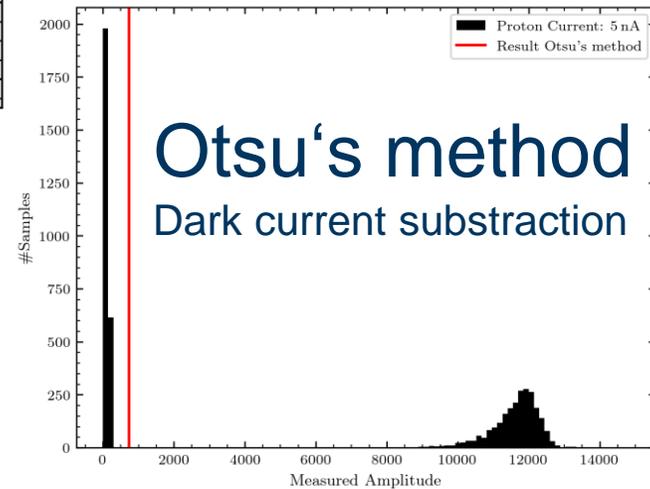
- Proton beam with a frequency of 85 MHz or half 42 MHz
- fA to 100 nA (25pA – 10nA , our experiment)
- Beam Modulated On/Off with 1 s pulse duration
- Option to use a diffuser in proton beam line (makes beam more homogenous)
- Diodes read out by AMS Test Kit
- 1D line array of 64 diodes
- Stage allows 2D imaging



Diode response : time structure

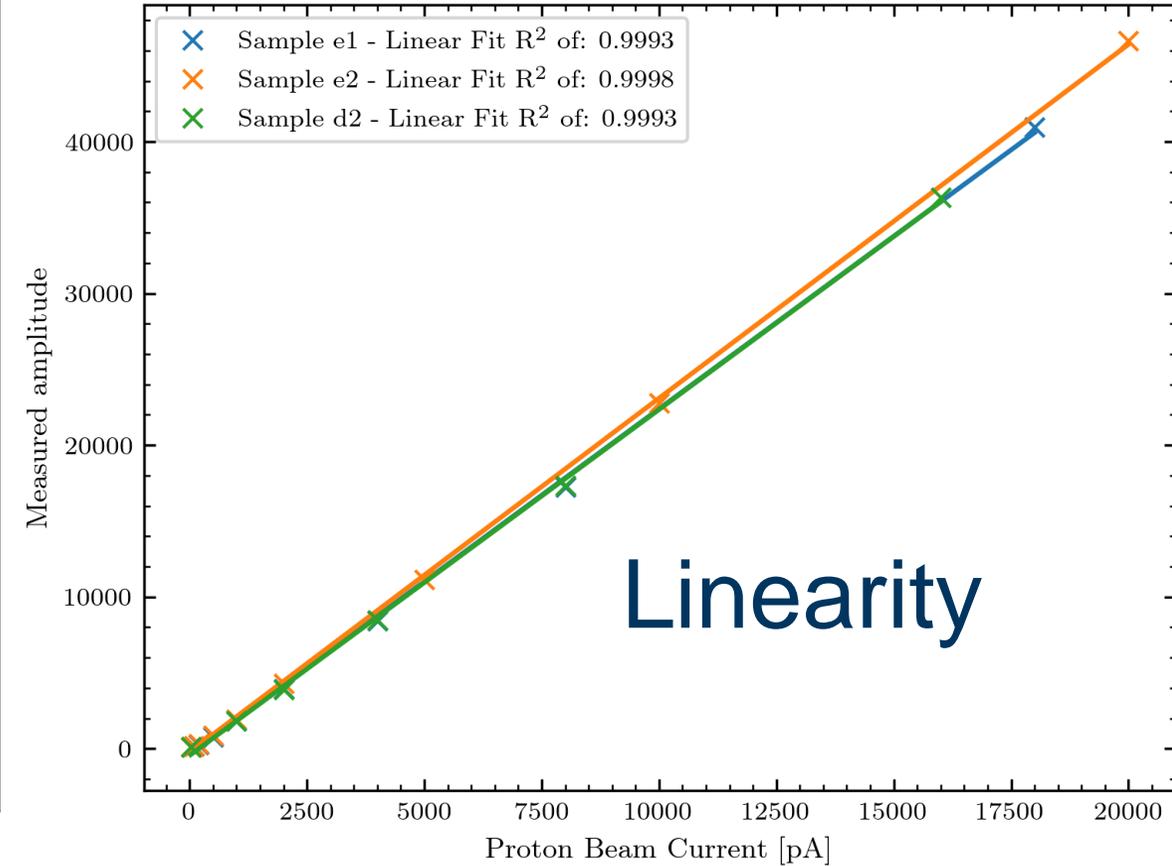
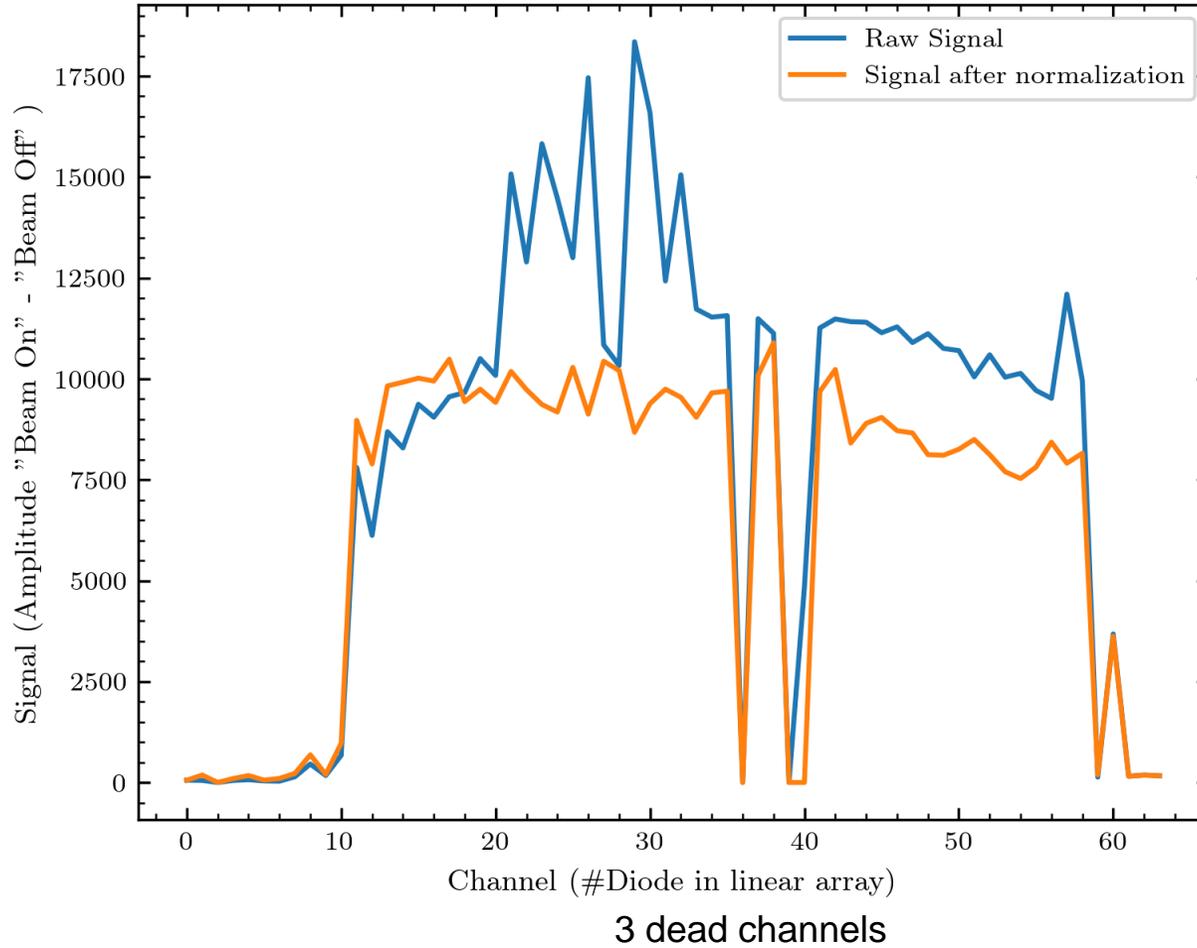


On/Off with 1 s pulse duration

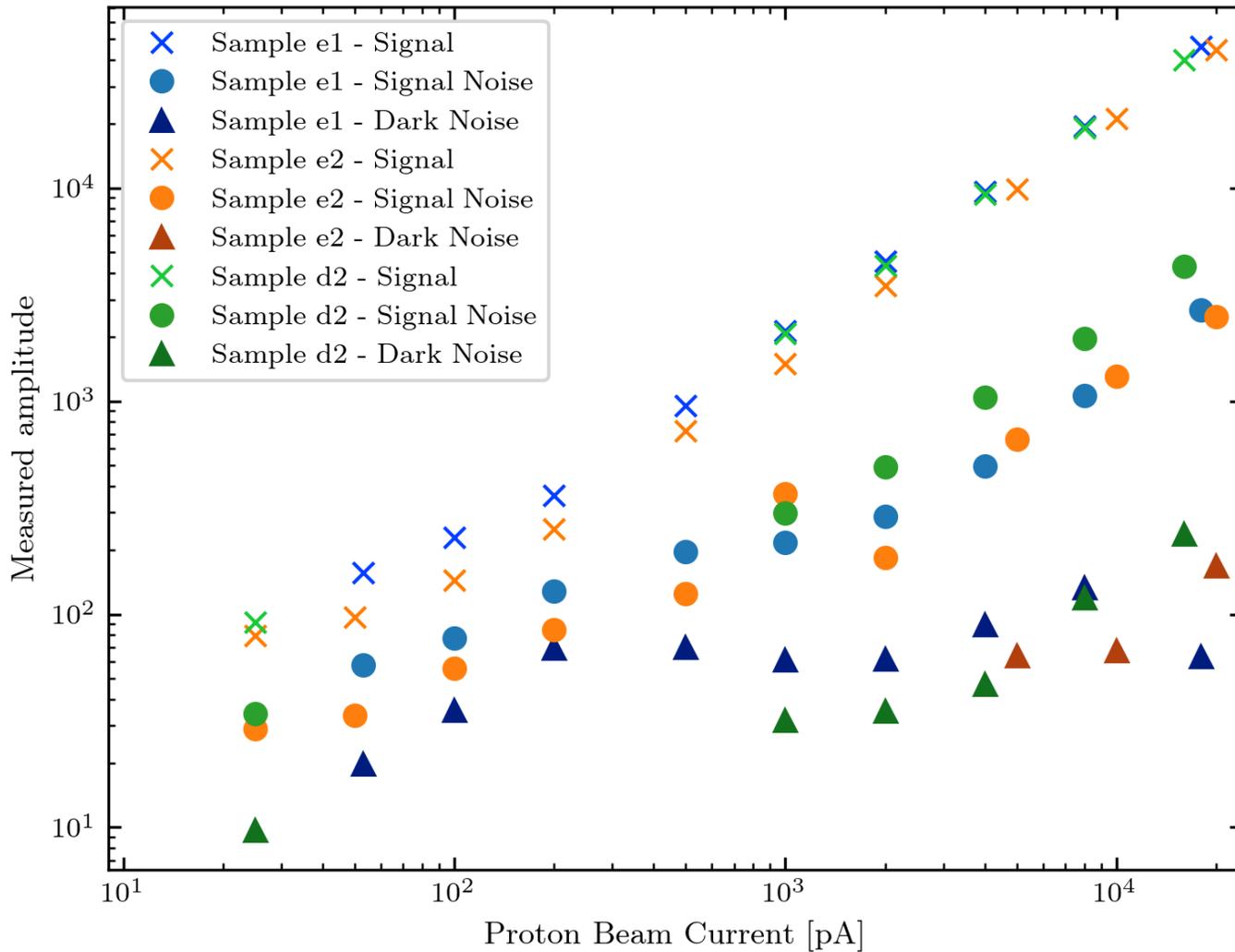


Normalizing the response (@5 nA)

courtesy of N. Broda (RUB)



Signal and noise for different diode structures (e1, e2, d2)



SENSITIVITY

CC2121 pin diode 1 μ m nid GaN

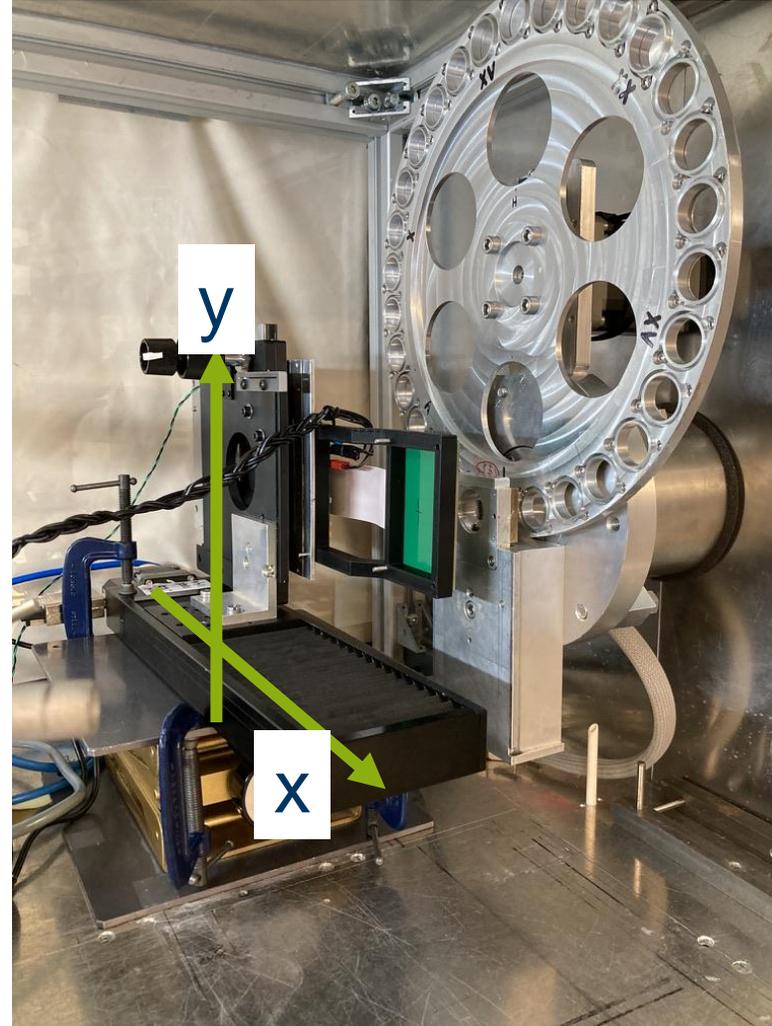
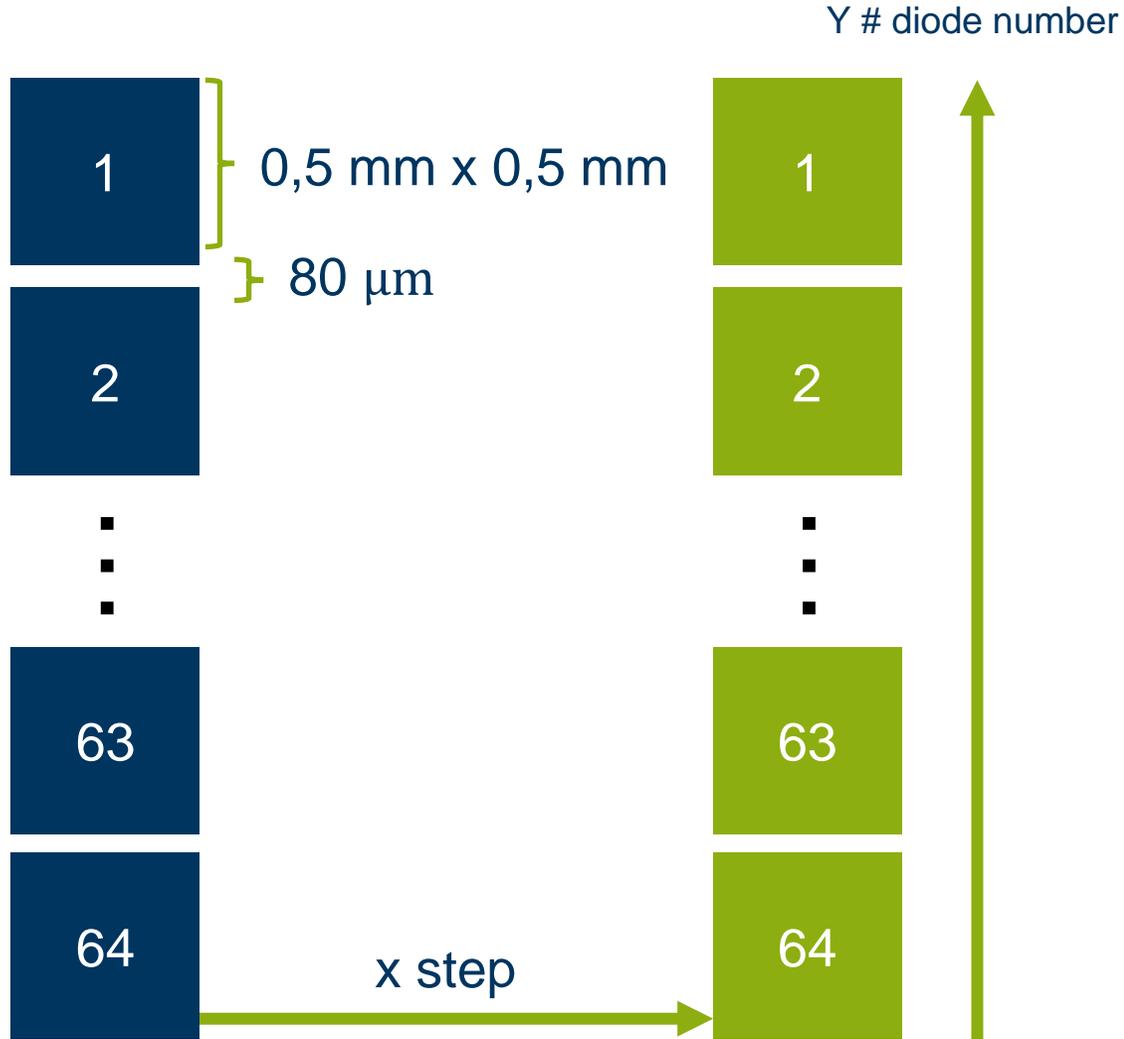
AMS :

Min detect. proton current density : 3 pA / cm²

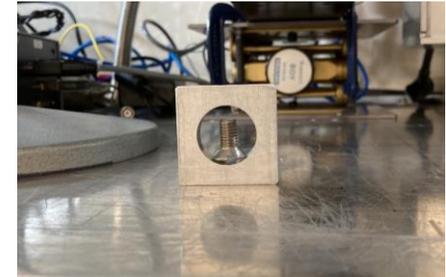
Min detect. proton current in the diode : 7.5 fA

Nb: 1.6 fA = 10000 protons / s

Proton beam imaging

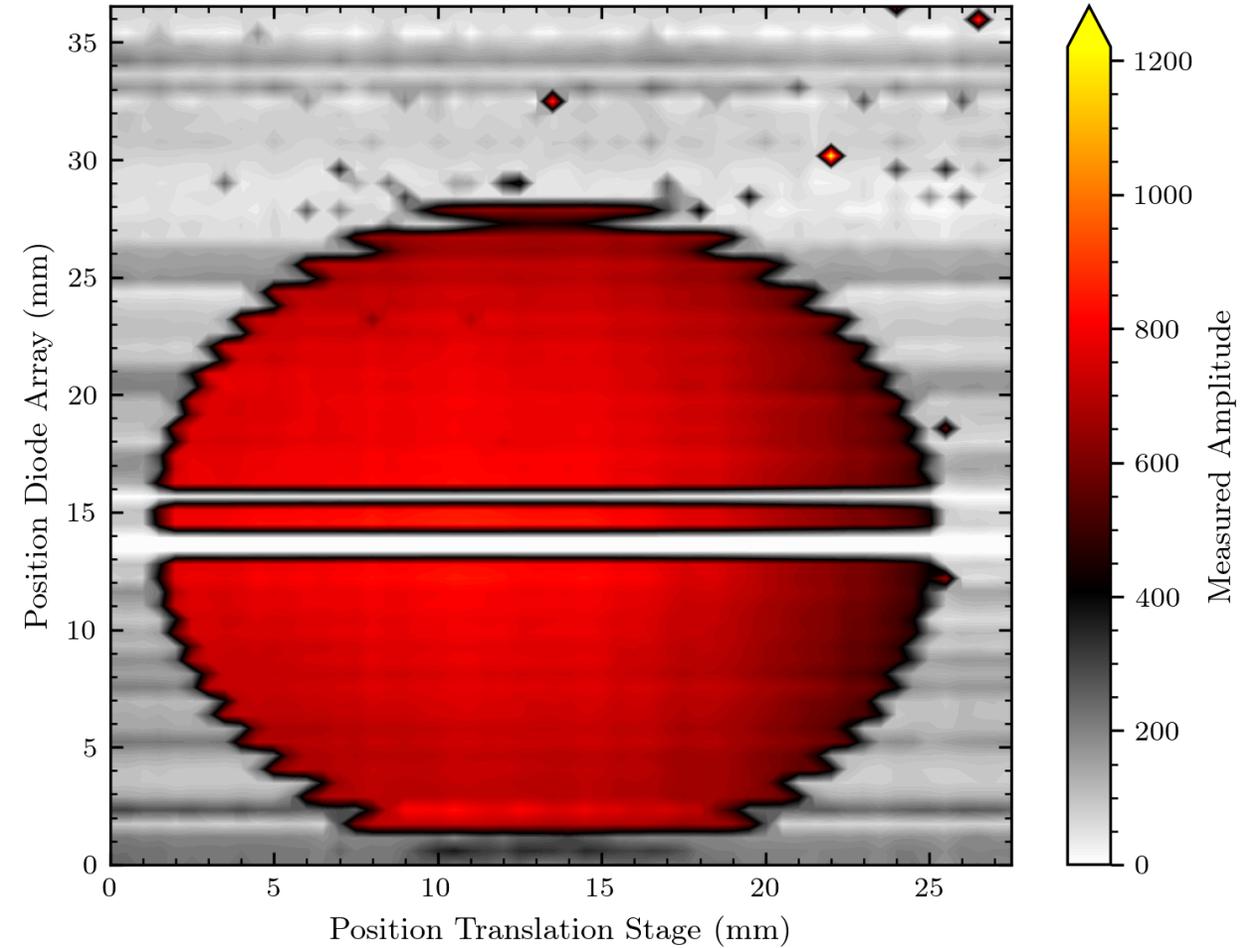
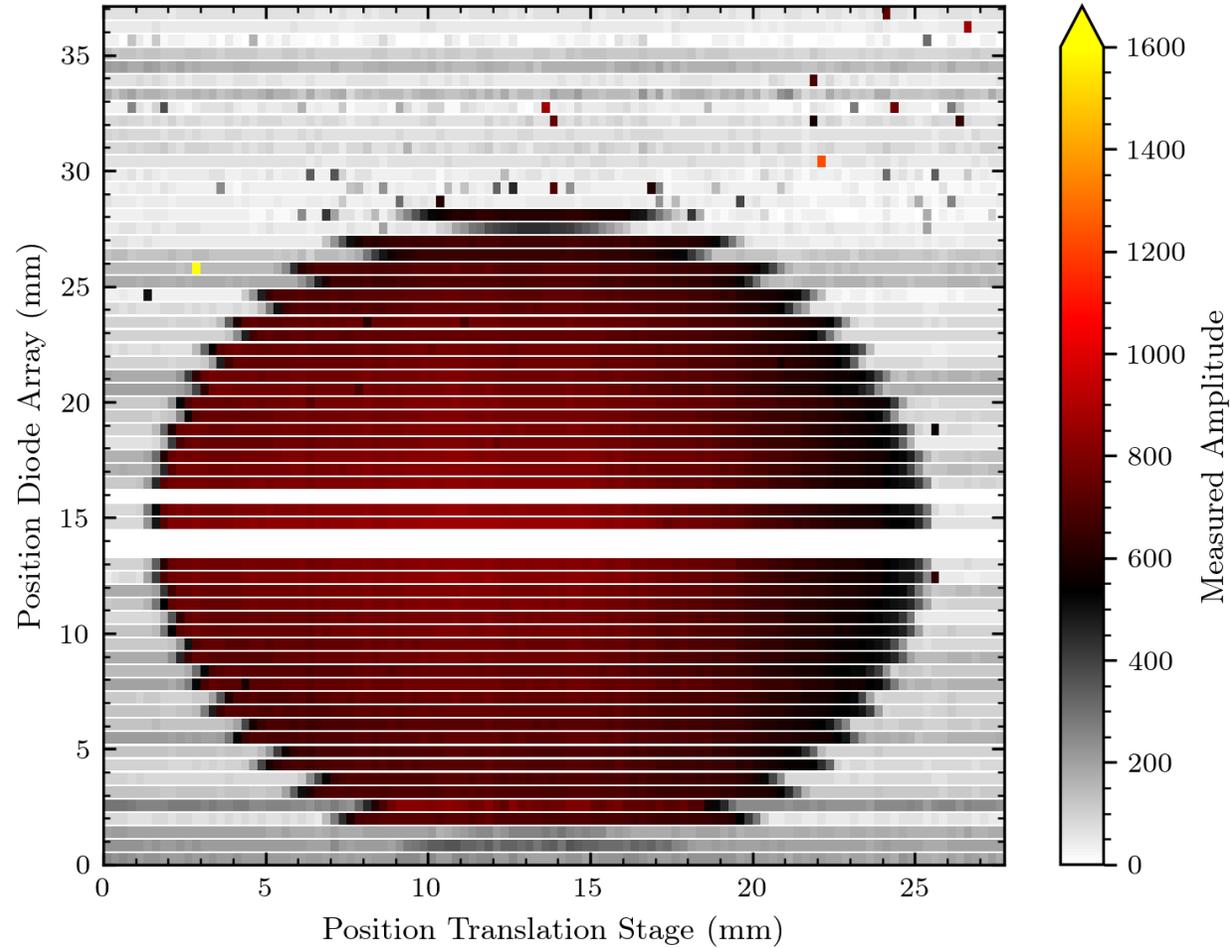


Empty round collimator imaging

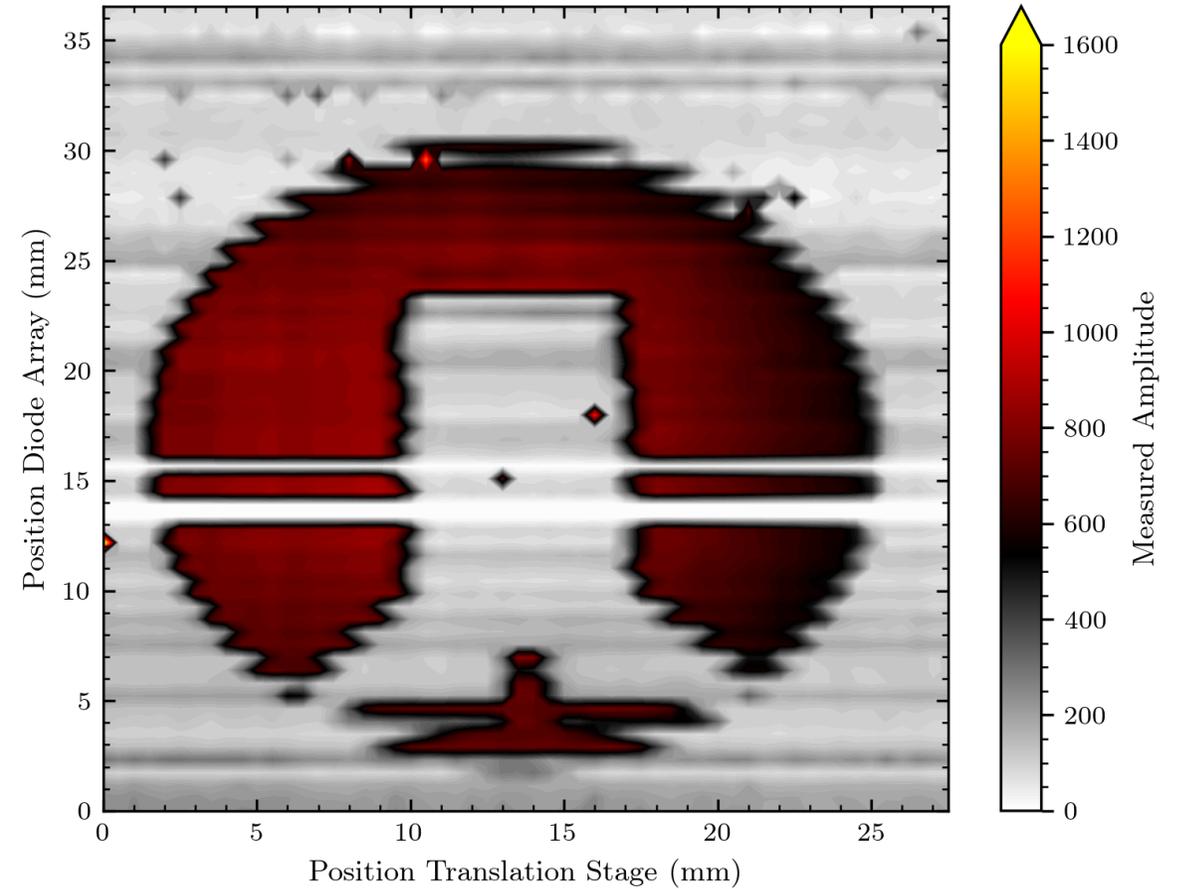
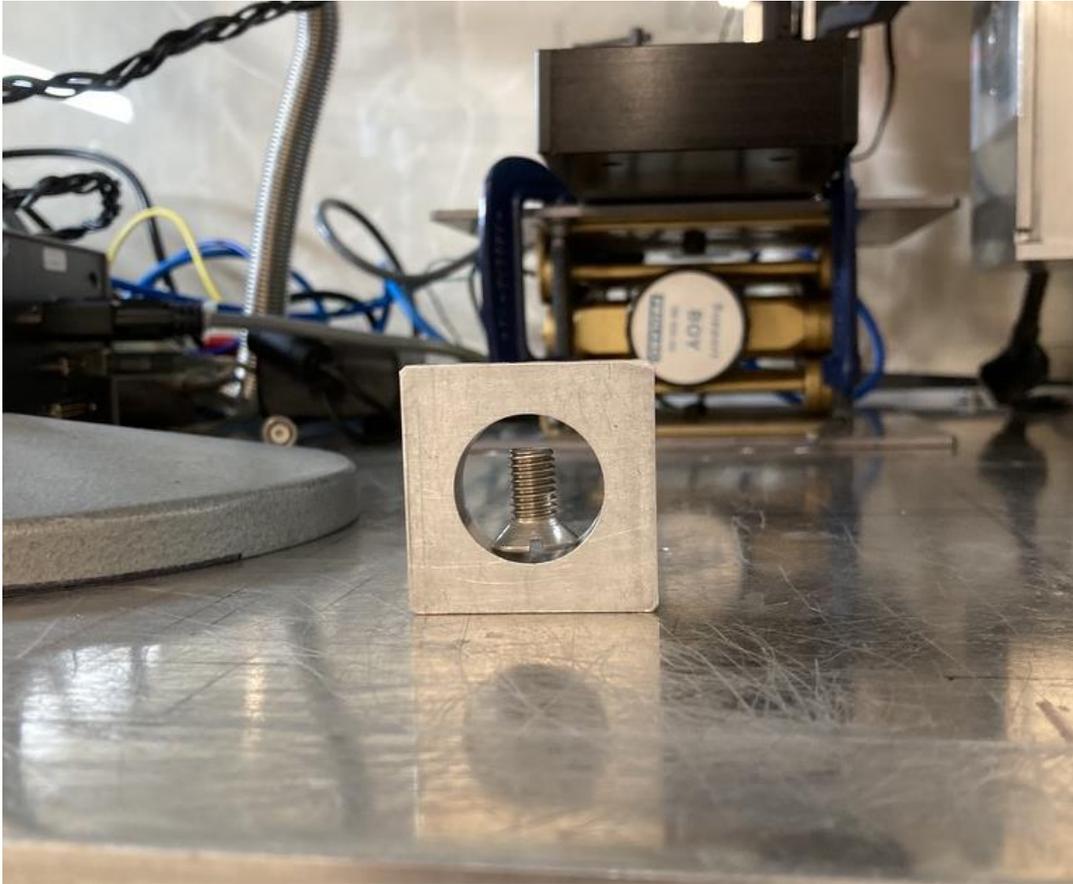


Imaging – real Image vs interpolated

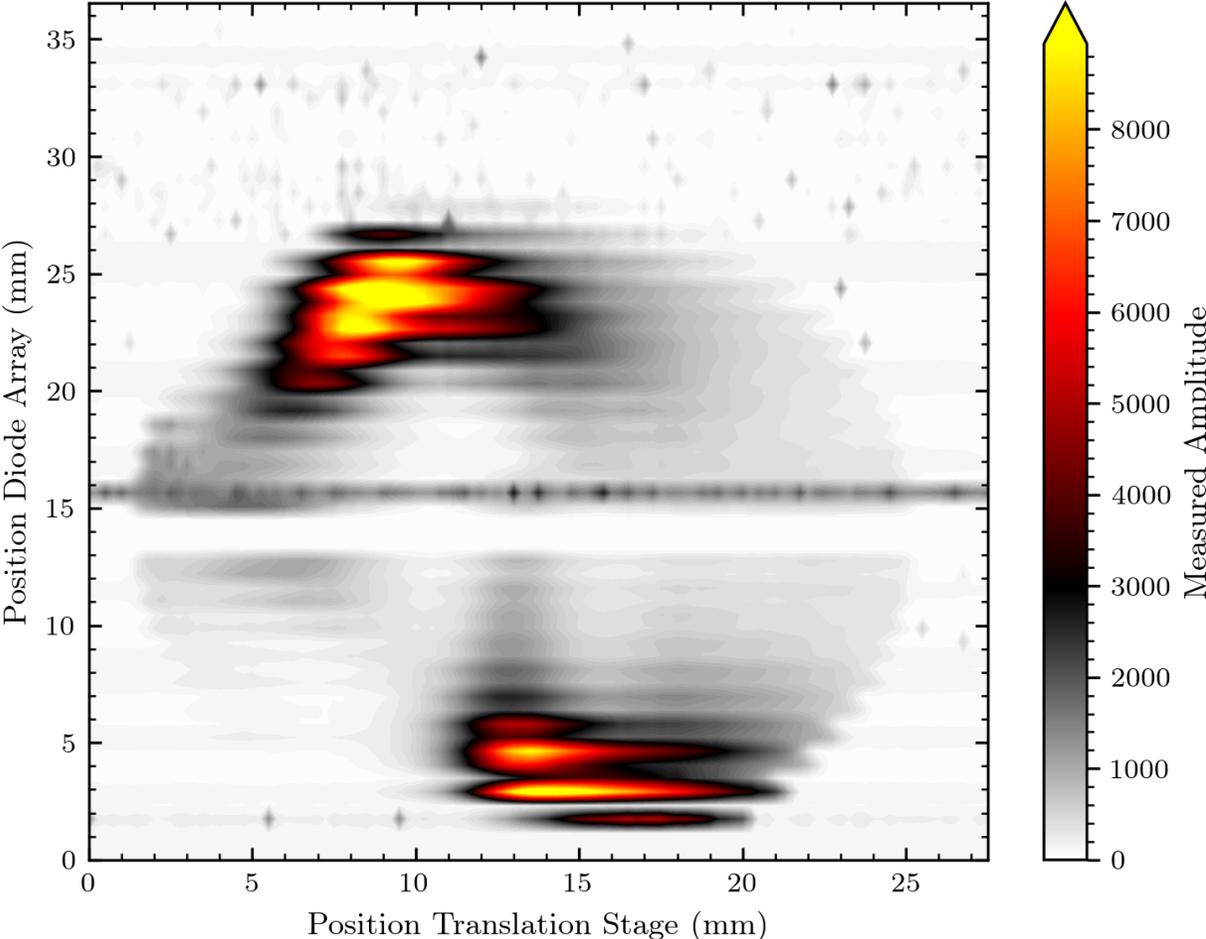
courtesy of N. Broda (RUB)



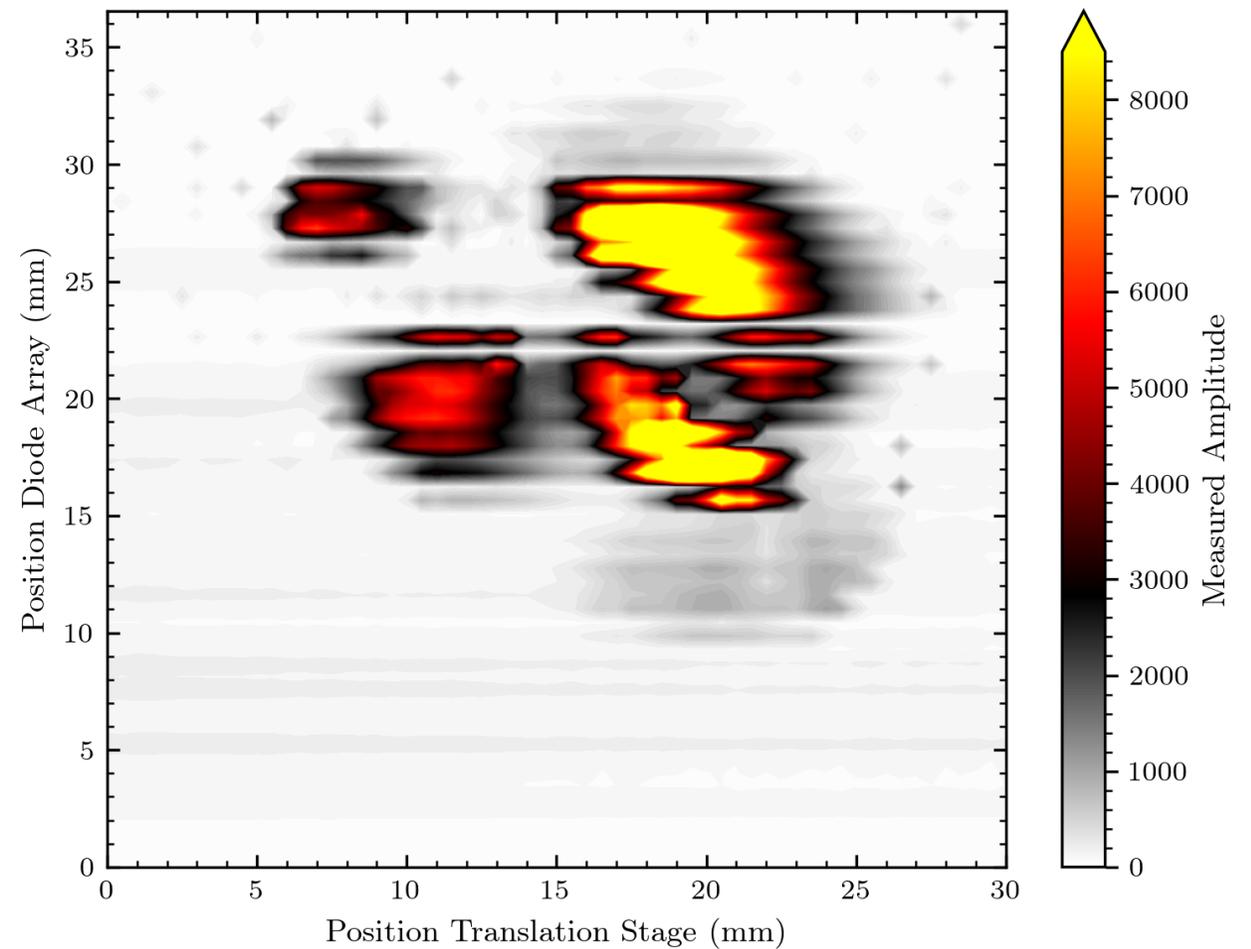
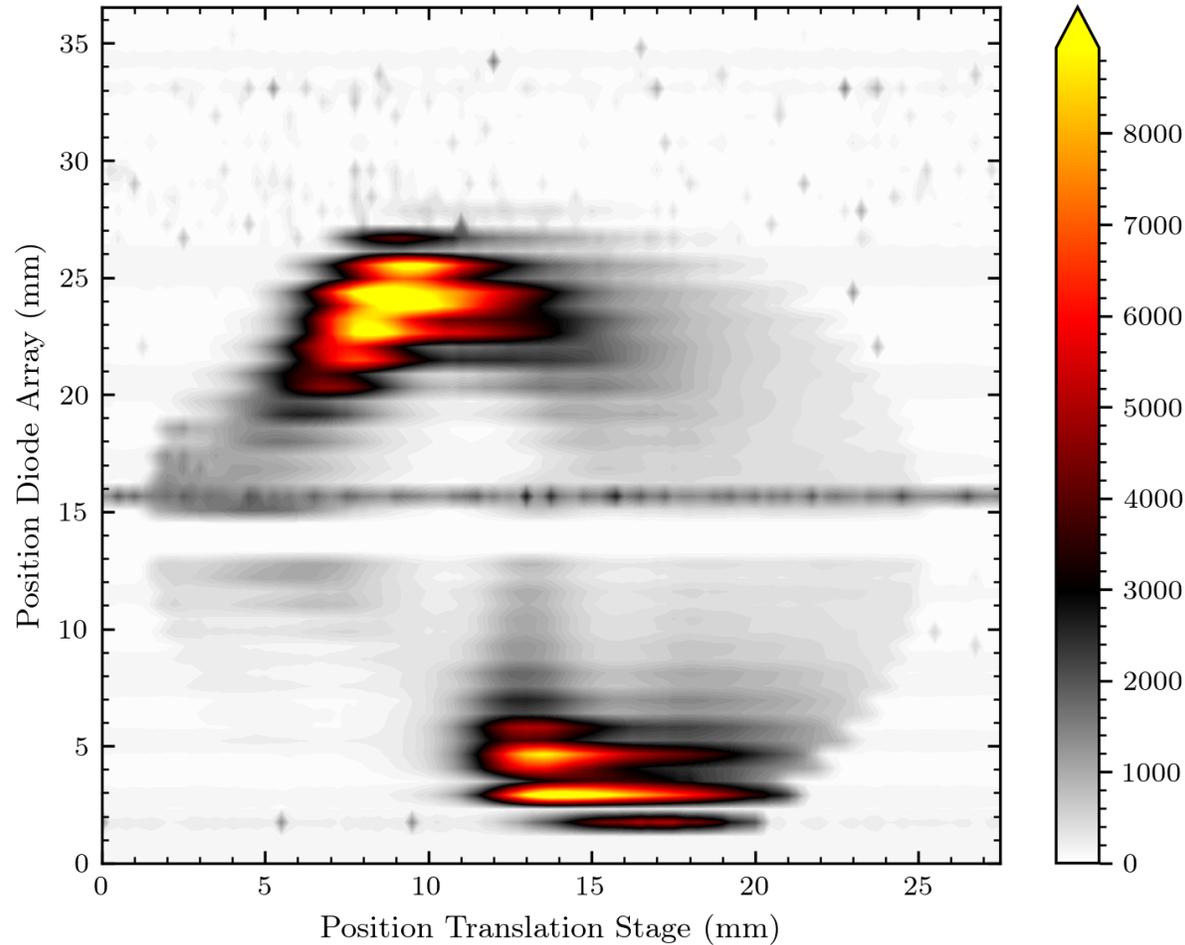
A (turn of the) screw



Beam image without diffuser (Al, 40 μm)



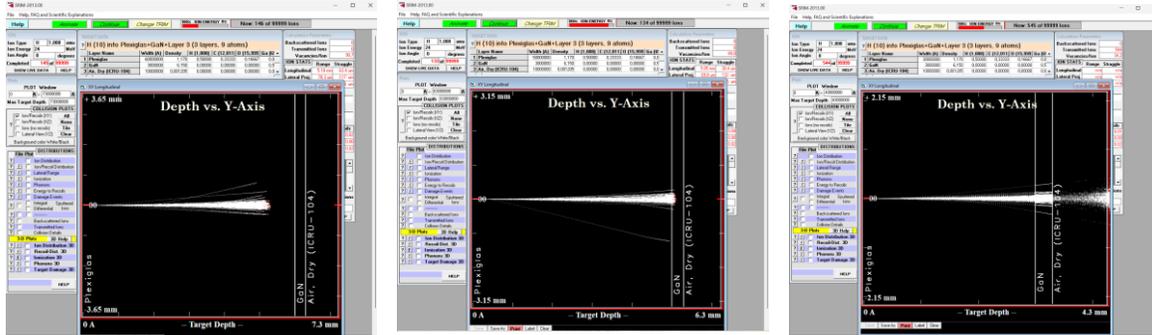
Beam structure 2.8 days later



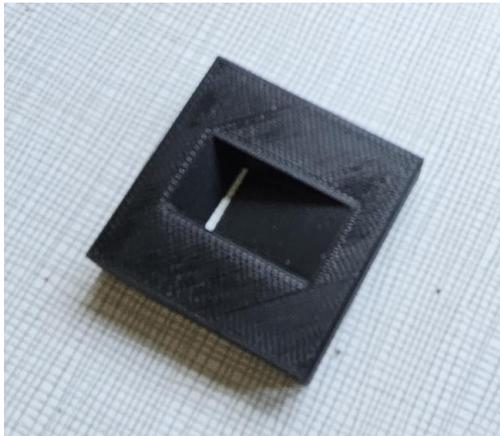
Application 1 : Beam energy monitoring 😊

Ongoing analysis 19/06/24

SRIM simulation



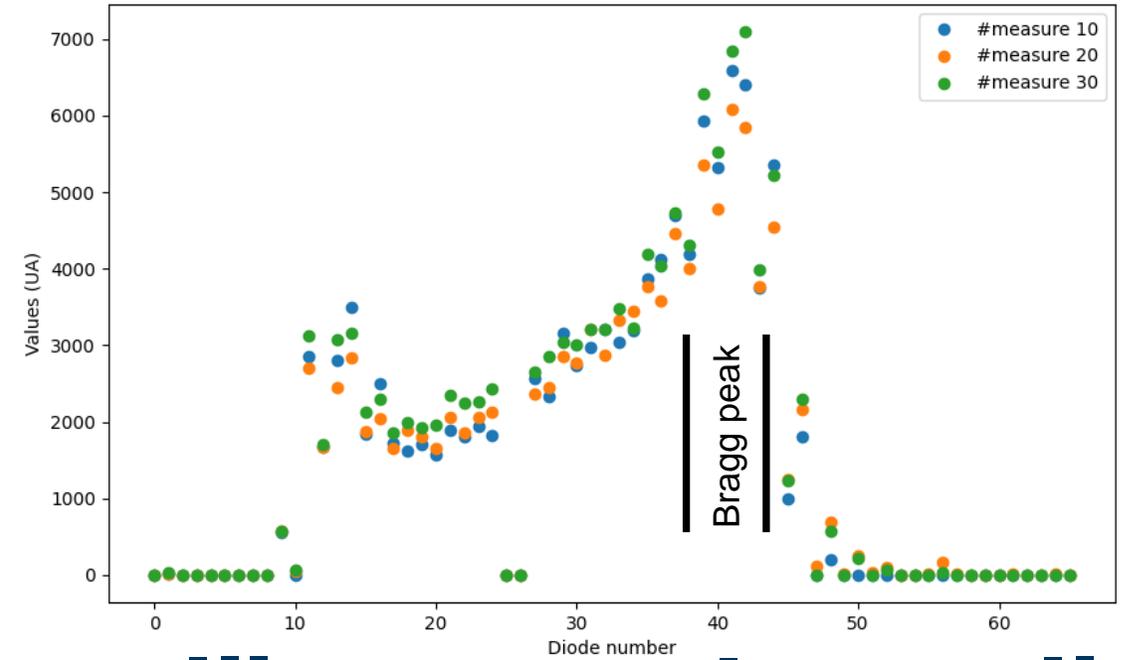
Bragg peak



3d printed trapezoid
(various shapes)

Cyrcé Proton beam

Charge -> deposited energy



Application 2 : Radiolysis of Biomolecules (Radiochem, IPHC)

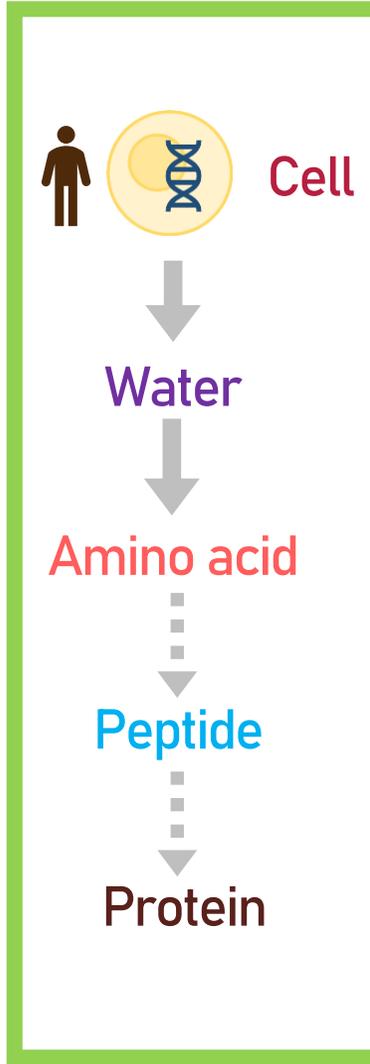
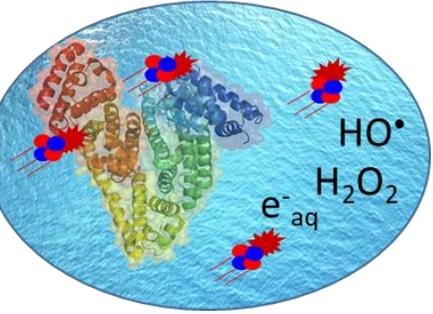
courtesy of Q. Raffy (IPHC, Strasbourg)

Radiolytic yield G :

$$G = 100 \cdot \frac{N_{\text{species/ion}}}{E}$$

In species per 100 eV

Water radiolysis
Radiolysis of biomolecules



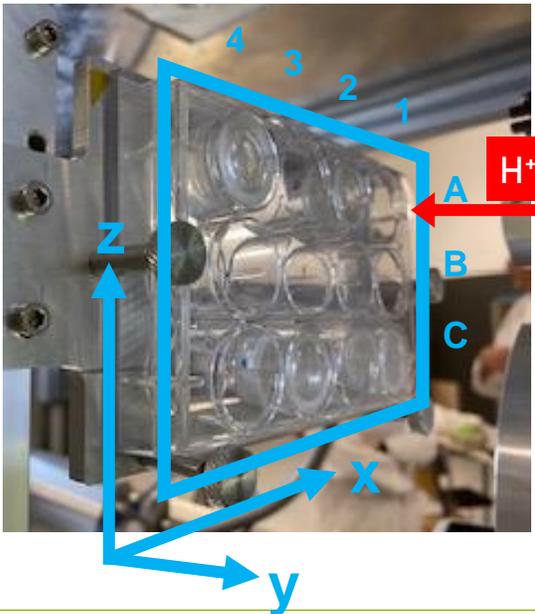
Determination of Radiolytic yields G:
→ **Determination of the dose (critical)**

➔ **Matrix, beam current monitoring (linearity pA to nA)**

- pA – 1 nA (long time exp.)
- 100 nA (short time exp.)

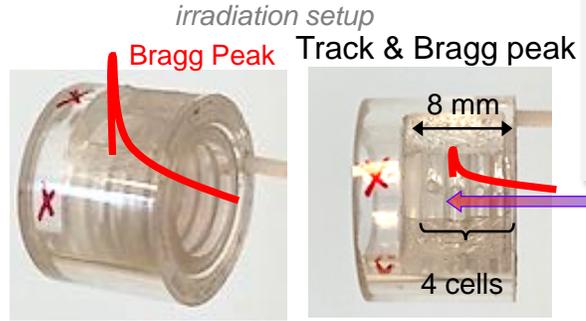
Radiolysis cells and support design

Mobile plate with 12 positions in front of the beam line



H⁺ 24 MeV

H⁺ (24,05 MeV) : 5,83 mm in water



Cell configurations
H⁺: 4 x 2 mm cell
Volume : 226 μL

1 cell in the "Fragments" region



Application 3 : Beam monitoring (IBA)

Industrial irradiation facilities

AERIAL (labcom, iphc)

→ High energy E-beam and X-rays (feerix)

x-ray beamline (5 MeV, 7 MeV)

electron beamline (10 MeV, maximum power 10 KW)

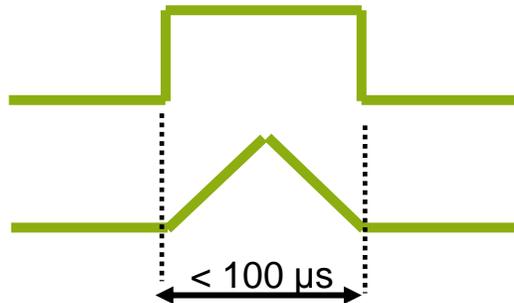


feerix®



Application 4 : Flash therapy, beam structure

- CAL, Nice
- WPE ?



temporal resolution measurement of the proton beam
(one diode is enough)

Outlook

- **More measurements in proton beam (CAL, WPE)**
 - Physics simulations
 - IBA system comparison (ionisation chambers, 1mm res.), pencil beam
- **Hadrontherapy (SiC), CNAO (500 MeV)** 
- **Optical setup for diode excitation (laser)**
 - Easier studying of AMS circuit parameters (fine tuning), capacitance, ...
- **Further process of data analysis (relation to image processing)**
- **2D array (11 x 11) and (k x 128) multiplexed**
- **Analog device testing**

TEAM EFFORT

IPHC, Strasbourg

L. The-Duc

C. Wabnitz

N. Arbor

S. Higuere

RUB, Bochum

A. Wieck

N. Broda

WPE, Essen

C. Bäumer

L. Parschat

CAL, Nice

J. Hérault

P. Hofverberg

M. Vidal

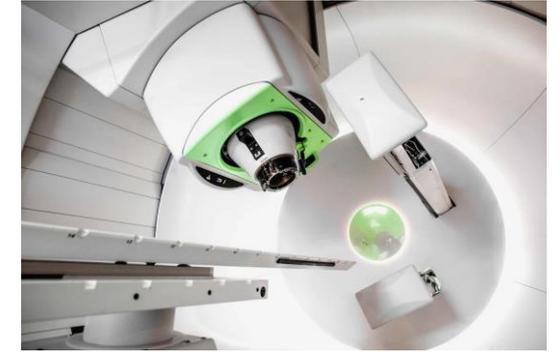
CRHEA, Nice

J-Y. Duboz

M. Siviero

M. Hugues

L. Lesourd



wpe West German
Proton Therapy Centre
Essen

CRHEA

RUB

ii!!!

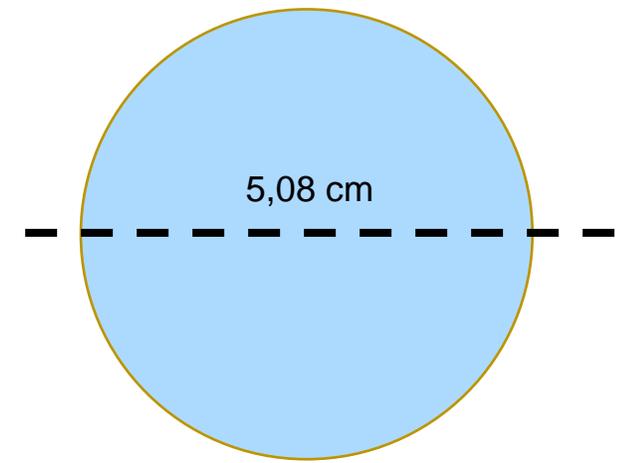
MATRIX

 **Antoine Lacassagne**
CENTRE DE LUTTE CONTRE LE CANCER
unicancer NICE

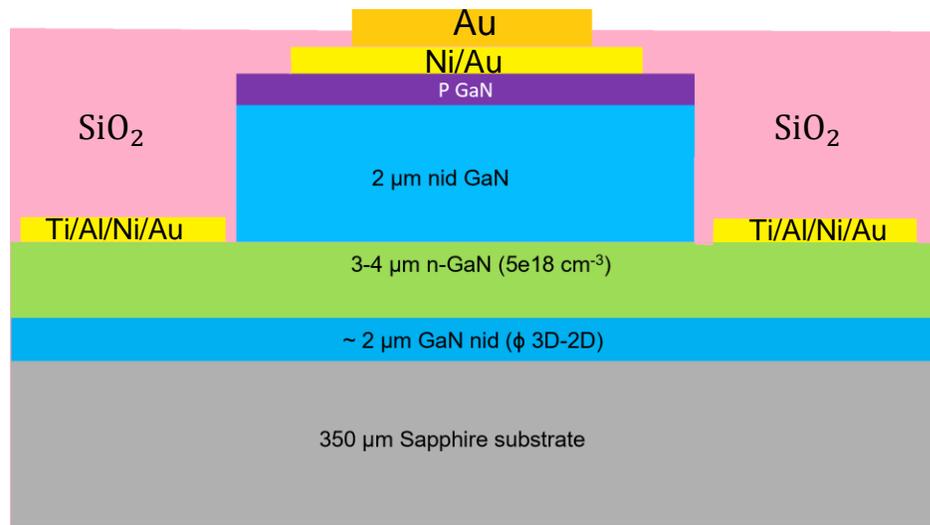
iPHC
Institut Pluridisciplinaire
Hubert CURIEN
STRASBOURG

 Université
franco-allemande
Deutsch-Französische
Hochschule

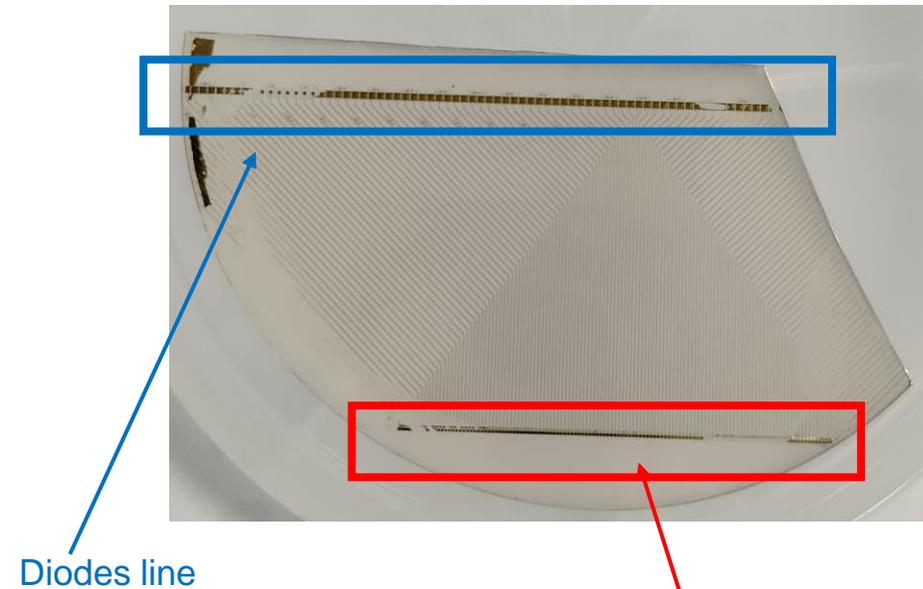
CC1606-02 (1/2 of a 2 inches wafer)



PIN DIODE



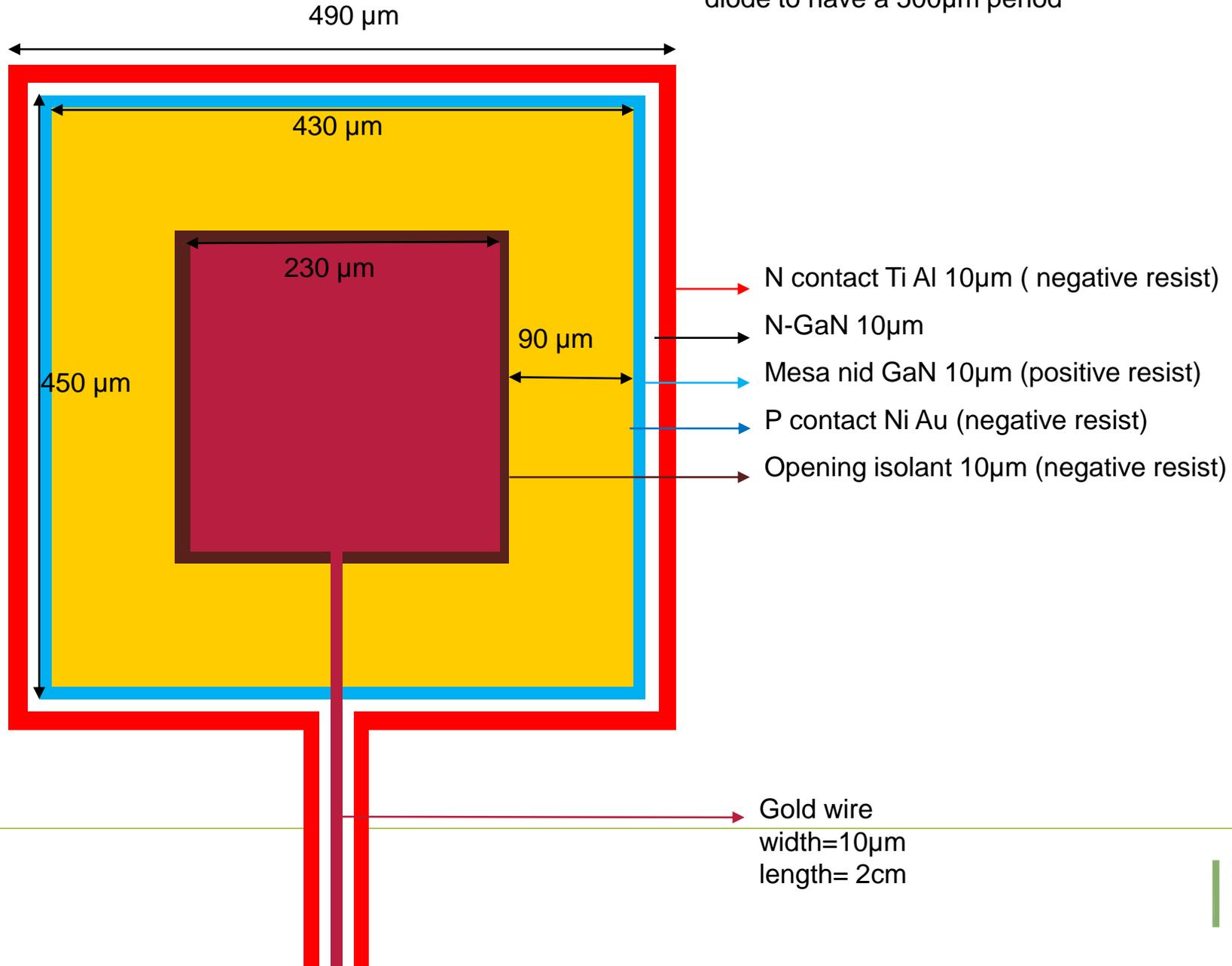
Diode cross section



Contacts for wiring

Mask – single diode plan view

Distanced 10 μ m from the next diode to have a 500 μ m period



Mask – single diode side view

